

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2000-038342

(43)Date of publication of application : 08.02.2000

(51)Int.Cl.

A61K 31/70

A61K 9/06

A61P 17/00

A61P 17/02

A61K 31/79

A61K 47/36

A61K 47/38

(21)Application number : 11-136255

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(22)Date of filing : 17.05.1999

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(30)Priority

Priority number : 10135060

Priority date : 18.05.1998

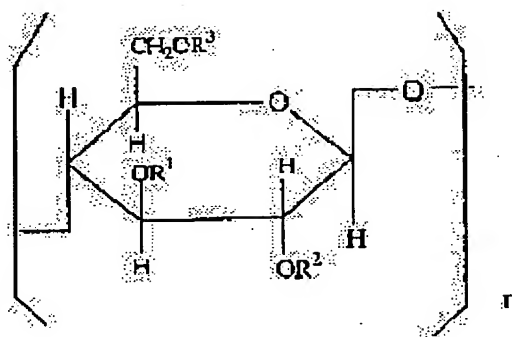
Priority country : JP

(54) PHARMACEUTICAL PREPARATION FOR RESTORING BEDSORE AND DAMAGED SKIN

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a pharmaceutical preparation for restoring bedsore and damaged skin in the form of an ointment containing active ingredients such as refined sugar and povidone-iodine having stability for a long period without using a shape retaining agent or a buffer agent, having extensibility and excellent in feeling of use.

SOLUTION: This pharmaceutical preparation for restoring bedsore and damaged skin contains 0.5-5.0 wt.% of at least one kind selective from the group consisting of a lithium salt, a sodium salt, a magnesium salt, a potassium salt, a calcium salt, a zinc salt and an ammonium salt of alginic acid or the salts of a derivative of polysaccharides represented by the following formula [R1, R2 and R3 may each be same or different and at least one kind thereof is carboxymethyl group; the remaining groups are each hydrogen atom, methyl group or ethyl group; the bond between mutual pyranose rings may be an α -1,4 bond or a β -1,4 bond; (n) is a natural number] as a stabilizer in the pharmaceutical preparation for restoring the bedsore and damaged skin containing 50-90 wt.% of a sugar, 0.5-10 wt.% of povidone-iodine and 1-20 wt.% of water.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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